



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Satoshi TAKANO

Application No.: 09/819,690

Filed: March 29, 2001

For: SEMICONDUCTOR MANUFACTURING METHOD, SUBSTRATE PROCESSING METHOD, AND SEMICONDUCTOR MANUFACTURING APPARATUS

Group Art Unit: 2825

Examiner: G. Lee

Docket No.: 109107

AMENDMENT UNDER 37 C.F.R. §1.111

Director of the U.S. Patent and Trademark Office  
Washington, D.C. 20231

Sir:

In reply to the November 7, 2003 Office Action, the statutory period for reply being extended by the attached Petition for Extension of Time, please amend the above-identified application as follows:

IN THE CLAIMS:

Please replace claims 1, 2, 3 and 6 as follows:

1. (Amended) A semiconductor manufacturing method, comprising the steps of:
- exchanging a substrate between a preliminary chamber and an external part;
- subjecting the substrate to predetermined processing in a process chamber; and
- transferring the substrate through a transfer chamber provided between said preliminary chamber and said process chamber,
- wherein said substrate transferring step comprises the following three steps:
- a first step of transferring said substrate, from said preliminary chamber to said transfer chamber;

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